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**School of Engineering**

B.TECH Electronics and Communication Engineering in Artificial Intelligence and Machine  
Mid Term Examination - May 2024

Duration : 90 Minutes  
Max Marks : 50

**Sem VI - G2UC606C - VLSI Design**General Instructions

Answer to the specific question asked

Draw neat, labelled diagrams wherever necessary

Approved data hand books are allowed subject to verification by the Invigilator

- 1) Explain about the diffusion. K2 (2)
- 2) Discuss the types of the metal semiconductor contacts, describe in brief K1 (3)
- 3) Distinguish between dry etching & wet etching. K2 (4)
- 4) Draw a RC ladder for Elmore delay with its propagation delay time, tpd. K2 (6)
- 5) Illustrate problems arise due to the scaling of MOSFET. K3 (6)
- 6) Explain the pinch-off condition in MOSFET with diagram. K3 (9)
- 7) Formulate the various critical parameters of Transistor scaling K4 (8)
  
- 8) Analyze Delay in CMOS. K4 (12)

**OR**

- (i) What is the accumulation voltage in MOSFET. (ii) An n-channel MOS transistor is made on a p-type Si substrate with  $N_a = 5 \times 10^{15} \text{ cm}^{-3}$ , intrinsic concentration of Si is  $1.5 \times 10^{10} \text{ cm}^{-3}$ . And  $V_t$  at room temperature is 0.259 eV. Find the inversion voltage. K4 (12)